

"Embedded Software in EUV Lithography Systems"

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Abstract

Extreme ultraviolet lithography is the technology used to pattern the finest details on the most advanced microchips. EUV lithography is currently a technology entirely unique to ASML. All ASML lithography systems make use of embedded software, which steers and controls EUV machines.

There are multiple challenges and constraints when designing and implementing embedded software. In this presentation, we will talk about these challenges and also provide practical examples on how embedded software is designed, implemented, deployed and maintained withing the EUV lithography systems.

Biography

Gerardo Santiago Flores is a Senior Software Architect at ASML San Diego with 10 years of experience working on lithography systems. Gerardo earned an M.S. in Embedded Systems from the Technical University of Eindhoven (TU/e) and a B.S. in Mechatronics Engineering from National University of Mexico (UNAM). During his work at ASML, Gerardo has worked at multiple subsystems within the EUV machine, guiding software teams with the design and implementation of embedded and application software.